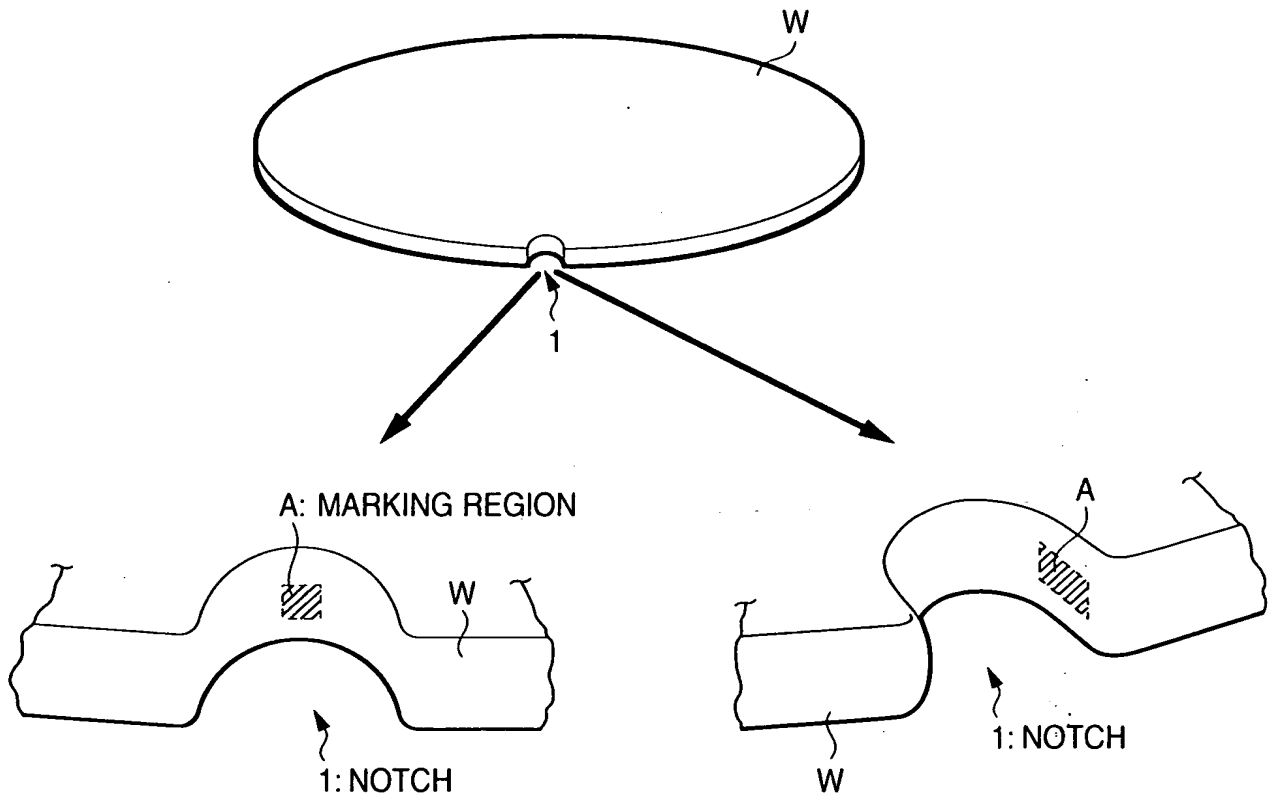
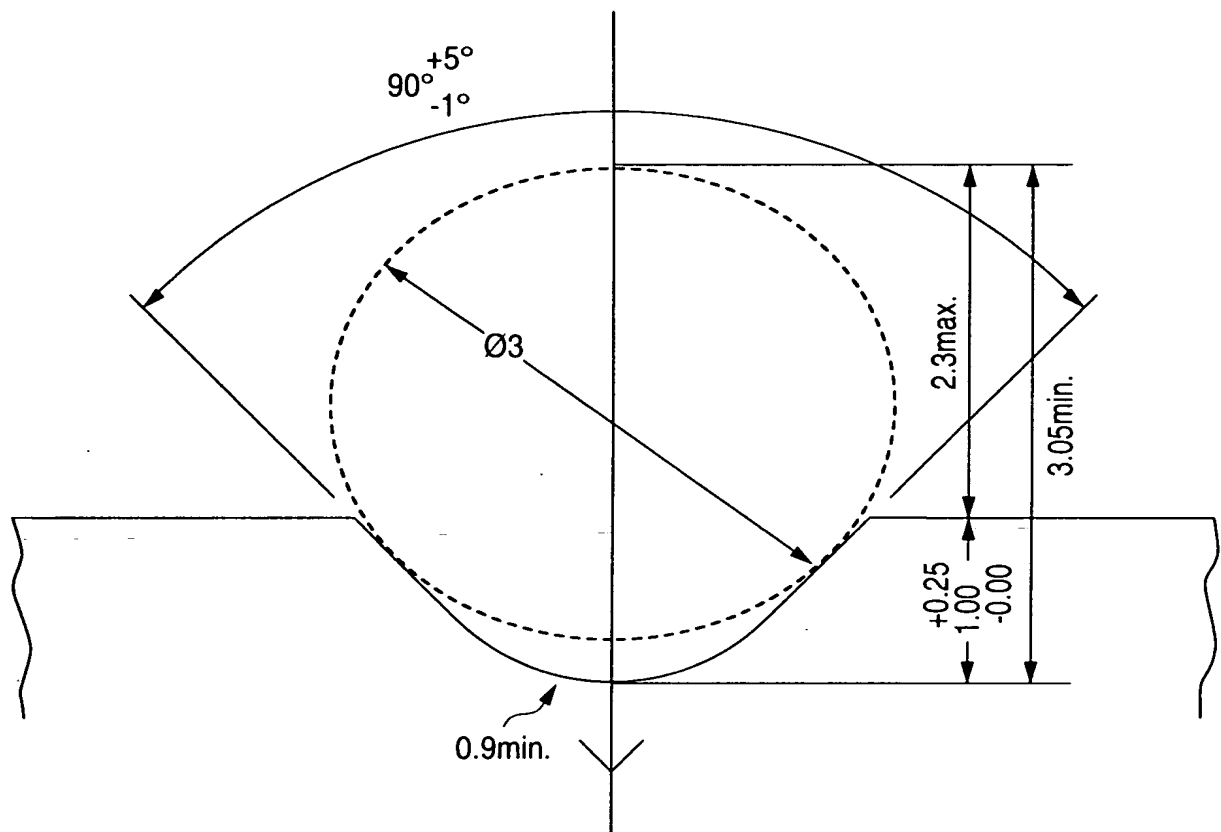


FIG. 1



EXPLANATORY VIEW SHOWING A SEMICONDUCTOR
WAFER ACCORDING TO THE INVENTION IN WHICH MARKING
IS CARRIED OUT ON A PORTION OF A NOTCH PORTION

FIG. 2



PLANE VIEW SHOWING A RELATIONSHIP BETWEEN A
SHAPE OF A NOTCH AND A PIN INSERTED INTO THE NOTCH

FIG. 3A

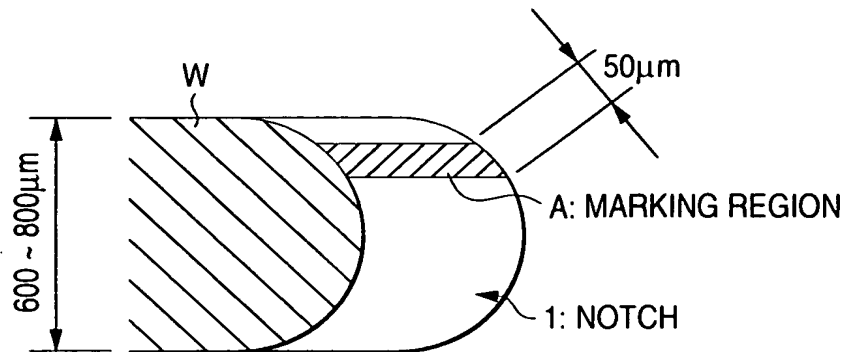


FIG. 3B

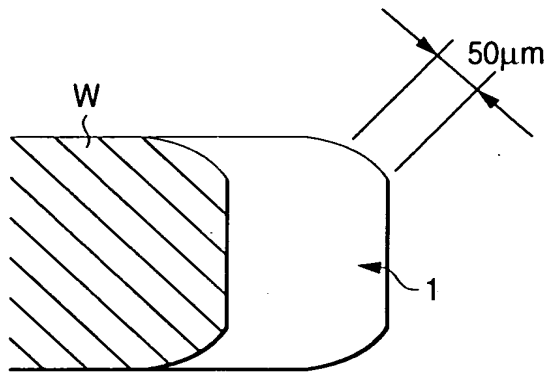
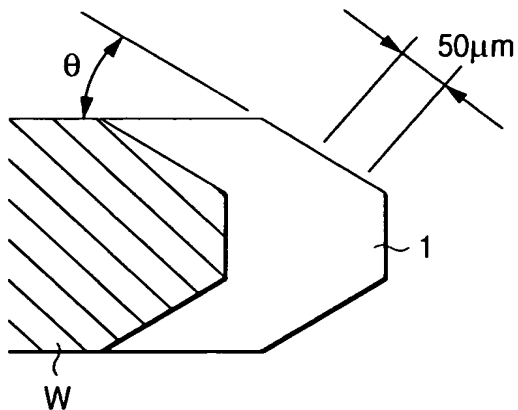


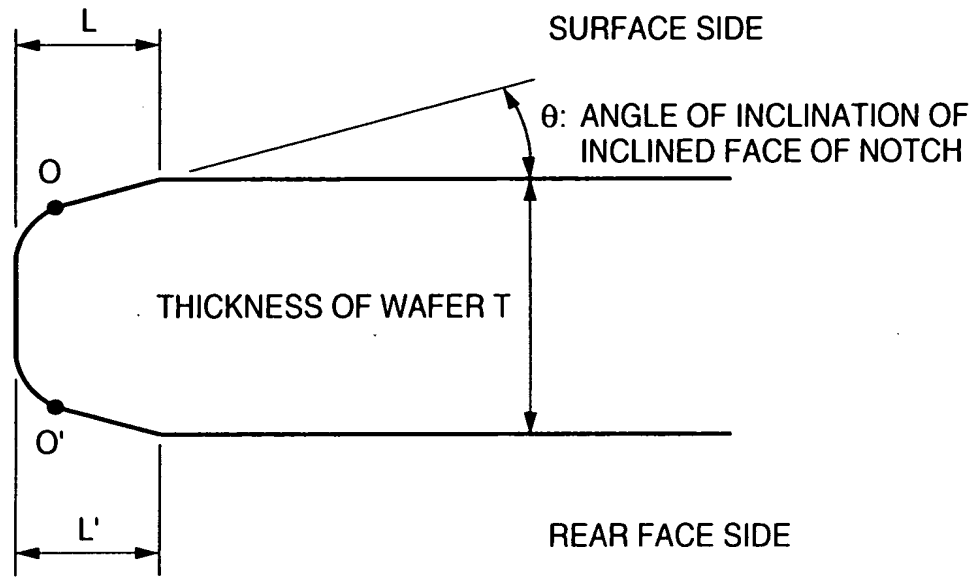
FIG. 3C



SECTIONAL VIEWS SHOWING EXAMPLES OF SECTIONAL SHAPES
OF A PERIPHERAL EDGE PORTION OF A SEMICONDUCTOR WAFER

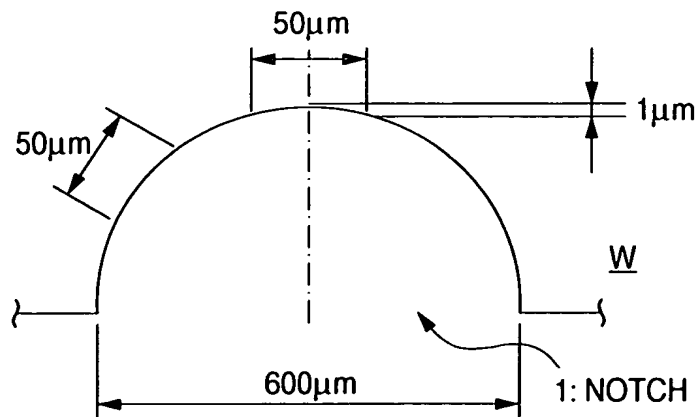
FIG. 4

HORIZONTAL DIMENSION
OF INCLINED FACE



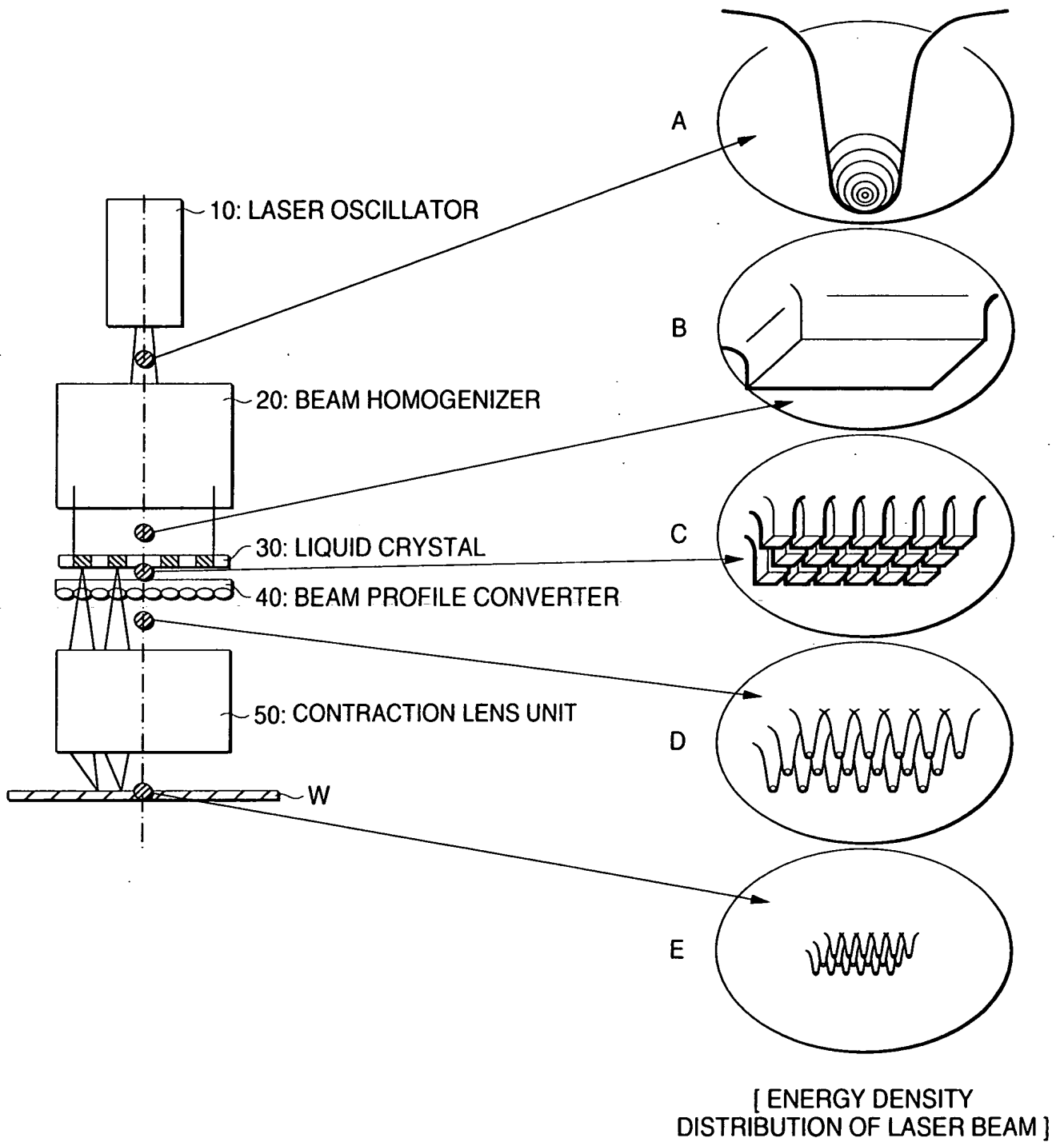
SECTIONAL VIEW SHOWING A SECTIONAL FACE OF A PERIPHERAL
EDGE PORTION ACCORDING TO AN EMBODIMENT OF THE INVENTION

FIG. 5




PLANE VIEW SHOWING A DIFFERENCE IN A DIMENSION OF A WALL
FACE IN A MARKING REGION OF AN INNER WALL FACE OF A NOTCH


FIG. 6

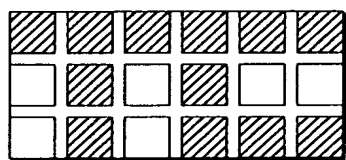


EXPLANATORY VIEW SCHEMATICALLY SHOWING A VERY SMALL DOT MARKING APPARATUS APPLIED TO THE INVENTION AND A PROCEDURE OF CONVERTING AN ENERGY DENSITY DISTRIBUTION (BEAM PROFILE) OF LASER BEAM

FIG. 7

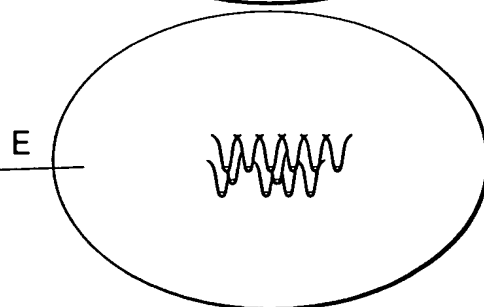
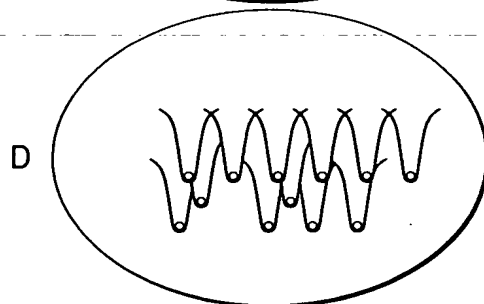
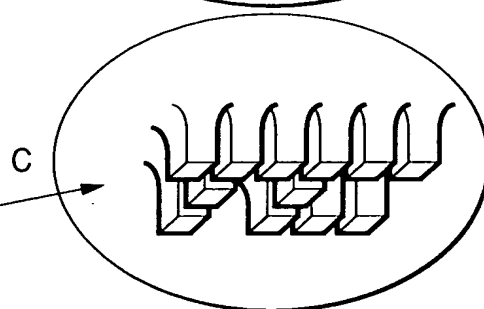
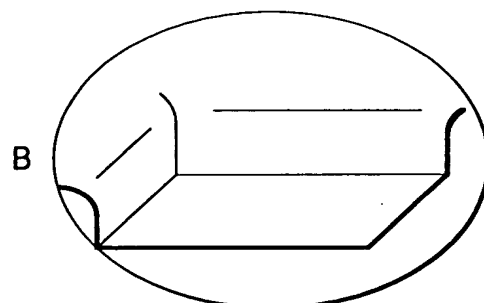
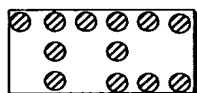
LIGHT TRANSMITTING PORTION
ON LIQUID CRYSTAL MASK 

LIGHT NON-TRANSMITTING PORTION
ON LIQUID CRYSTAL MASK 



30: LIQUID CRYSTAL MASK

DOT MARKS ON SURFACE
OF SEMICONDUCTOR WAFER



EXPLANATORY VIEW SCHEMATICALLY SHOWING DOT MARKS
FORMED IN ACCORDANCE WITH A DISPLAY PATTERN OF A LIQUID
CRYSTAL MASK IN A MARKING APPARATUS AND A PROCEDURE
OF CONVERTING AN ENERGY DISTRIBUTION OF LASER BEAM

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PLANE VIEW SHOWING ALPHANUMERIC CHARACTERS BY DOT MARKS
INSCRIBED ON AN INCLINED FACE OF A NOTCH OF A SEMICONDUCTOR WAFER